

### UNIVERSITET Optical Replica Synthesizer and EuXFEL Laser Heater

#### Volker Ziemann Department for Physics and Astronomy Uppsala University



## Theme

- Uppsala University is involved in activities to manipulate bright electron bunches with an external laser
  - for diagnostic purposes
    - Optical Replica Synthsizer
  - for beam stability
    - Laser Heater
- Other systems in a similar spirit are (that you already do) are EO or slicing







## Optical Replica Synthesizer in FLASH





#### The original ORS collaboration:

G. Angelova, VZ, *Uppsala University* P. van der Meulen, P. Salén, M. Larsson, *Stockholm University* H. Schlarb, J. Bödewadt,E. Saldin, E. Schneidmiller, M. Yurkov, F. Löhl, A. Winter, DESY S. Khan, *DELTA, TU Dortmund* A. Meseck, *BESSY* 



**Optical Replica** 



# The Idea behind the ORS



longitudinal

electron distribution

- Problem: measure ultra-short bunches in the 10s of fs range: EOS, TEO, LOLA, ORS
  - too fast for electronics (10 Gs/s, 100 ps)
  - but laser folks know (autocorrelation, FROG)
- Solution: make an optical copy of the electron bunch and analyze that with laser methods.



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## The Seed Laser





- Er-fiber ring-oscillator (~1550 nm) phase locked to RF (micro-timing)
- Booster amplifier
- 2nd harmonic generation to 772 nm
- CPA 2001 regenerative amplifier on loan from Stockholm
- Pockels cell fire to let the light pulse out (macro-timing)
- 0.7 mJ/pulse, 150 fs to 2 ps
- Safety shutters (ND and other)
- Diagnostics: Frog, virtual waist



#### Laser Transfer Line and OS0



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## The Undulators







- Electromagnets
- Designed and built by Scanditronix, Vislanda, Sweden
- Period 20 cm
- 5+2 periods
- 4 power supplies per magnet
- Modulator=(V)eronica
- Radiator=(H)ilda



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## GRENOUILLE



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- Cyclidrical lens makes horizontal strip
- Fresnel biprism creates crossing wavefronts in thick SHG crystal → auto-correlator
- Effective thickness of SHG crystal varies with viewing angle
  → Spectrally resolved
- Second double cylidrical lens images onto camera
- Horizontally  $\rightarrow$  time
- Vertically  $\rightarrow$  spectrum
- GRENOUILLE USB 8-50 controlled by VideoFROG software

Picture from Trebino's book





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## **Experiment Preparation: Transverse Overlap**



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Electron orbit < 0.1 mm

Electron and Laserposition on OTR equal before and after modulator

Modulato



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10

X (mm)

15

20

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## Temporal Overlap of sub-ps Electron bunch und Laser pulse





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Laser Modulator OTR OTR Chicane Chicane



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#### ...finally: Single-shot FROGs





- From radiator (HILDA)
- Significant tuning with OS2 Setup
- long/short Grenouille
- First shortE/shortL because of intensity
- Here shortE/longL during SASE conditions at 700 MeV (13 nm)
- Unfortunately no simultaneous LOLA measurement
- Parasitic operation

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What's next?

- ORS undulators are installed in the sFLASH beam line.
- sFLASH HHG laser can deliver 30 mJ in IR, but presently mirrors are optimized for harmonics around 30 nm.
- New laser beamline for 800 and 270 nm (tripler) will be installed this fall...
- ...for EEHG experiments (hopefully) in conjunction with Replica experiments early 2012 (stiff competition for beam time in FLASH)



# **ORS** Conclusions



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- Installed and commissioned the optical replica synthesizer in FLASH since fall 2007
- We managed to hit the electron bunch with laser
  - can be used to measure longitudinal-transverse correlations in long (few ps) bunches
- Eventually recorded online FROG traces from the shortpulse GRENOUILLE
  - unfortunately no simultaneous LOLA measurements
- Undulators were reinstalled in the sFLASH beam line and using the HHG laser and new laser beam line they will be used for EEHG and hopefully ORS experiments.







- Call by the Swedish Research Council for EuXFEL contributions in March 2008
- We were triggered by the electron-laser theme
- Succesful bid, approved May 2008, but money was only released in October 2010!
- Swedish in-kind contribution to the EuXFEL

 – UU: Gergana Angelova-Hamberg, Mathias Hamberg, Vitaliy Goryashko (from September)

• So why does EuXFEL need one and what is it?



Why ...



- Electrons are born in the photo cathode with a very small momentum spread (~3 keV)
  - makes them susceptible to microbunching instability on their travel through the linear accelerator and bunching chicanes
- Add Landau damping (decoherence) in a wellcontrolled way to increase momentum spread
  - induce moderate momentum modulation by passing a laser over the electrons in an undulator
  - and smear out by coupling some of the angular spread into the longitudinal plane



How ...



- Pass IR laser over beam in undulator  $\rightarrow$  modulate dE
- $\rm R_{_{5\!2}}$  of 2nd leg of chicane couples 'transverse heat' into the longitudinal plane and smears out the modulation





### Parameters



- Will use 1030 nm photons
- Operate between 110 and 160 MeV
- Permanent undulator with variable gap
- 8+2 periods of I=74 mm
- Chicane offset 30 mm
- Second half has  $R_{_{55}} = 0.003/2 \text{ m}, R_{_{52}} = 0.030 \text{ m}$
- Pulse energy up to 50 uJ (2.5 MW, 20ps)
- Beta functions 9 and 12 m,  $\sigma$  ~ 0.2 mm











- Use the non-converted "red" photons from the first frequency doubling (red2green) stage
  - Inherently locked in timing to the parent UV photons for the entire pulse train
  - Bandpass filter to separate
  - Intensity according to Ingo Will is 30 to max 50 µJ depending on the pulse flattening scheme. This is adequate for routine operation, but for start-up and commissioning more is desirable (LCLS has 200 µJ available).
- Plan: study stability of photons (intensity, pointing, M2)
- Critical issue: additional laser amplifier stage (~100 kEuro according to Ingo Will, not in our budget, but MAC ok'ed it)
  - we need to follow the gun laser development

LIPPSAL A





- Long (~50 m) transport path through 'hostile' environment such as the vertical shaft
- Evacuated pipe to avoid dn/dT-wandering
  - actually need moderate vacuum but will use ion pumps to avoid mechanical noise
- Mirror mounts and pointing stability
  - passive stability to counteract fast jitter
  - slow feedback near undulator to counteract drifts
- Dielectric mirrors, use "spill" for target practice



#### **Chicane Layout**







## **Undulator Magnet**



SCANDITRONIX

Maanet

- Variable gap
- Gap > 30 mm
- 110..160 MeV
- L<sub>0</sub>=74 mm
- 8+2 periods
- B<sub>0</sub>=0.11..0.27 T

Courtesy of

European



### Hardware



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#### 28

- Diagnostic: fast photo-diode and oscilloscope (20 ps pulses) laser and synchrotron light

Screen before and after the undulator

Diagnostic: OTR for electrons and diffuse

Control: delay stage in laser hut





for laser

Longitudinal

Control: in periscope

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0.02

 $\begin{smallmatrix} 0.015 \\ M_{10} \\ 0.01 \\ 0.005 \\ 0.005 \\ 0.005 \\ 0.015 \\ 0$ 

0.0

 $\sigma_L = \sigma_L^0$ 

 $\sigma_{xb} = \sigma_L^0$ 

 $\sigma_{vb} = \sigma_L^0$ 

 $\dot{\mathbf{X}} = \mathbf{0}$ 

Y = 0

-75

0.02

0.015

0.01

0.005

0.0

0.02

Λ(Δγ<sub>0</sub>) [(keV)<sup>-1</sup>] 0.010 0.005

 $V(\Delta \gamma_0)$  [(keV)<sup>-1</sup>]

-50

 $\sigma_L = \sigma_L^0$ 

 $\sigma_{xb} = \sigma_L^0$ 

 $\sigma_{vb} = \sigma_L^0$ 

Y = 0

-75 -50

 $\sigma_L = \sigma_L^0$ 

 $\begin{array}{l} \sigma_{yb} = \sigma_L^0 \\ \mathbf{X} = \mathbf{0} \end{array}$ 

 $\mathbf{Y} = \mathbf{0}$ 

 $\sigma_{xb} = 1.5 \sigma_L^0$ 

-50

-75

-25

0

 $m_e c^2 \Delta \gamma_0$  [keV]

25

 $X = 0.5 \sigma_{r}^{0}$ 

-25

0

 $m_{e}c^{2}\Delta y_{0}$  [keV]

-25

0

 $m_e c^2 \Delta \gamma_0 \text{ [keV]}$ 

25

 $\sigma_{L}^{0} = 0.3 \text{ mm}$ 

50

75

 $P_I = 1 \text{ MW}$ 

50

75

25

#### Tolerances

 $\sigma_{L}^{0} = 0.3 \text{ mm}$ 

 $P_I = 1 \text{ MW}$ 

0.02

0.0

0.02

 $\begin{smallmatrix} 10.0 \\ \Lambda^{\rm (Vl_0)} & (\rm [(keV)^{-1}] \\ 0.005 & 0.005 \end{smallmatrix}$ 

0.0

0.02

 $\begin{smallmatrix} 1 \\ \Lambda^{(V_{A0})} & 0.015 \\ 0.010 & 0.005 \\ 0.005 & 0.005$ 

0.0

[ 0.015 0.01 ((keV)<sup>-1</sup>) 0.005

 $\sigma_{r}^{0} = 0.3 \text{ mm}$ 

50

75

 $\sigma_{I}^{0} = 0.3 \text{ mm}$ 

 $P_I = 1 \text{ MW}$ 

 $P_{I} = 1 \text{ MW}$ 

 $\sigma_L = 1.25 \sigma_r^0$ 

 $\sigma_{xb} = \sigma_L^0$ 

 $\sigma_{vb} = \sigma_{I}^{0}$ 

 $\dot{\mathbf{X}} = \mathbf{0}$ 

Y = 0

75

 $\sigma_L = \sigma_L^0$ 

 $\sigma_{xb} = \sigma_L^0$ 

 $\sigma_{yb} = \sigma_L^0$ 

 $X = \sigma_I^0$ 

Y = 0

-75

-50

 $\sigma_L = 1.5 \sigma_L^0$ 

 $\sigma_{xb} = 1.5 \sigma_L^0$ 

 $\sigma_{yb} = \sigma_L^0$ X = 0

Y = 0

-75 -50

-25

-25

0

m c2Av. [keV]

25

50

 $\sigma_{L}^{0} = 0.3 \text{ mm}$ 

 $P_{L} = 1.5 \text{ MW}$ 

50

75

75

50

25

0

 $m_e c^2 \Delta \gamma_0$  [keV]

25

50

 $\sigma_L^0 = 0.3 \text{ mm}$ 

 $P_L = 1 \text{ MW}$ 

75



• Size ~20%

• Offset  $\sim \sigma/2$ 

 Elliptic, ok, if we increase laser size

• Angle <  $\sim \sigma/L$ 



0.0

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25

0

 $m_e c^2 \Delta \gamma_0$  [keV]

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## Diagnostics on Laser Tables

Initial Setup

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- photon waist size and position
- control transverse position
- Online Monitoring
  - photon beam position (4Q)
  - photon beam size (camera)
  - Timing (diode)
- Stabilization



• Use signals from near-farfield, x,x' cameras after dielectric mirrors to compensate drifts with 2 upstream mirrors.

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### Timeline



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|  | 2010 | 0  |          |      | 2011     |                                  |     |      | 2012 |     |   |                                      | 2013                                    |                                |     |        | 2014  |       |       |       | Т            |       |
|--|------|----|----------|------|----------|----------------------------------|-----|------|------|-----|---|--------------------------------------|---|--------------------------------|-----|--------|-------|-------|-------|-------|--------------|-------|
|  | Q1   | Q2 | Q3       | Q4   | Q1       | Q2                               | Q3  | Q4   | Q1   | Q2  | Q3                                      | Q4                                   | Q1                                      | Q2                             | Q3  | Q4     | Q1    | Q2    | Q3    | Q4    | T            |       |
| Overall strategy                       |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | Ī            |       |
| Simulation/Tolerances                  |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | T            |       |
| Technical design and drafting          |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | T            |       |
| Fabrication                            |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | T            |       |
| Installation                           |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | T            |       |
| Commissioning                          |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | I            |       |
|  |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | I            |       |
| What laser system?                     |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | Ι            |       |
|  |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | I            |       |
| Undulator:                             |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | Ι            |       |
| Specification                          |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | I            |       |
| Tender                                 |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | Ι            |       |
| Fabrication                            |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | I            |       |
| Testing/field measurments              |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | I            |       |
| Installation                           |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       | I            |       |
|  |      |    |          |      |          |                                  |     |      |      |     |   |                                      |   |                                |     |        |       |       |       |       |              |       |
| Other components with default schedule |      |    | Ļ г      | NL   |          |                                  |     |      |      |     |   |                                      |   | T                              |     |        |       |       | liek  |       | ant aritaria | Data  |
| Chicane dipole magnets                 |      |    | ⊢⊦       | N    | 0        |                                  |     | IV.  | nie  | 510 | ne                                      |                                      |   | +                              |     | A      | CO    | mp    | lisi  | ime   | ent criteria | Date  |
| Electron vacuum components             |      |    | <b>⊢</b> | M    | 1        | Kick-off meeting                 |     |      |      | E   | Exchange of documents completed         |                                      |   |                                |     |        | Q3-10 |       |       |       |              |       |
| Electron diagnostics                   |      |    |          | _M   | 2        | Simulation infrastructure set up |     |      |      |     |   | P                                    | Preliminary design report               |                                |     |        |       |       | Q4-10 |       |              |       |
| Laser beam line optics                 |      |    | Ļι       | M    | 3        | Design report                    |     |      |      |     |   | A                                    | Agreement on all critical parameters    |                                |     |        |       |       | Q3-11 |       |              |       |
| Laser vacuum components                |      |    | $\perp$  | M    | 4        | Undulator specification          |     |      |      |     |   | S                                    | Specifications completed, tendering     |                                |     |        |       |       | Q3-11 |       |              |       |
| Laser diagnostics                      |      |    |          |      |          |                                  |     |      |      |     | de                                      | documents ready                      |   |                                |     |        |       |       |       |       |              |       |
|  |      |    | ſ        | M    | 5        | Undulator contract               |     |      |      |     |   |                                      | C                                       | Contract award after tendering |     |        |       |       |       | Q4-11 |              |       |
|  |      |    | Ē        | M    | 5        | Laser system concept             |     |      |      |     |   |                                      | C                                       | Conceptual design agreed       |     |        |       |       |       | Q4-11 |              |       |
|  |      |    | ľ        | M    | 7        | Laser system design              |     |      |      |     |   |                                      | F                                       | Final design completed, TDR    |     |        |       |       |       | 01-12 |              |       |
|  |      |    | h        | M    | 2        | Undulator                        |     |      |      |     |   | 1 n                                  | Delivery of undulator                   |                                |     |        |       |       | 02-12 |       |              |       |
|  |      |    | - 1      | M    | 5        | Vacuum chambers                  |     |      |      | 1 D | Delivery of vacuum chambers and support |                                      |   |                                |     |        | 03-12 |       |       |       |              |       |
|  |      |    |          | IVIS | <b>7</b> | vacuum unambers                  |     |      |      |     | etructuree                              |                                      |   |                                |     | 0.0-12 |       |       |       |       |              |       |
|  |      |    | H        | 141  |          | Optical components               |     |      |      |     | 1 2                                     | Delivery of all entired components   |   |                                |     |        |       | 02.10 |       |       |              |       |
|  |      |    | ŀ        | NA4  | 4        | Field measurements               |     |      |      |     |   | 무단                                   | Undulates field measurements examinated |                                |     |        |       |       | 04.12 |       |              |       |
|  |      |    | ŀ        | MI   | 4        | Field measurements               |     |      |      |     |   | 10                                   | Undulator field measurements completed  |                                |     |        |       |       | Q4-12 |       |              |       |
|  |      |    | H        | M1   | 2        | Installation and integration     |     |      |      |     | In                                      | Installation & Integration completed |   |                                |     |        | Q2-13 |       |       |       |              |       |
|  |      |    | L        | M1   | 3        | Cor                              | nmi | ssio | ning |     |   |                                      |   | C                              | omn | nissi  | onin  | g co  | omp   | leteo | d            | Q3-13 |

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- Laser heater is a Swedish in-kind contribution to the EuXFEL project done by Uppsala University.
- Started for real early 2011.
- Simulations and tolerance calculations are in progress. (Martin Dohlus and Vitaliy Goryashko)
- We are working on engineering solutions (Mathias Hamberg, Niklas Johansson, Masih Noor)
- Undulator parameters are fixed and draft of tender is in the works.

### **Backup slides**



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## **Optical Station 1**



Essential for timing: Laser + Synchrotron radiation







Modulator

35

41 OS2

Radiato

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# Seed Laser and Modulator

- Seed laser must overlap electron bunch and provide sufficient strength to modulate the energy
- probably Ti:Sapphire
- Length: a few ps, say 10 ps
- Synchronization to bunch RF and electron gun
- Power: 100 MW, 1 mJ/pulse, 5 Hz
- modulation amplitude:  $dp/p \sim 10^{-3}$
- Need dog-leg to shine laser onto electron trajectory
- Undulator with about 5 periods

Coupling between laser and electrons

$$\Delta U = e \int (\vec{E}.d\vec{s}) = e \int E_x v_x dt$$



Some gain, some loose, depending on initial phase





## **Radiator Undulator**



- Electrons have longitudinal density modulation and can radiate coherently.
- Each electron slice oscillates in undulator (like an antenna) and all contributions are added in phase.
- Number of periods *N* determines the length of the light pulse that an electron emits  $\rightarrow$  short undulator
- Need to propagate replica pulse to diagnostic section



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- 8-50: 17 fs
- 5 Periods
  - 4 µm/13 fs
- Wavefront tilt
- Dispersion in optics on OS2
- Bent(?) mirrors
- Plasmaoscillations(?)

## Resolution

Grenouille: Datenblatt von
 Swamp Optics

| GRENOUILLE model:                       | 8-9USB   | 8-20USB       | 8-50USB        | 8-300USB     | 8-500USB     |  |  |  |  |  |
|---|--|---------------|----------------|--------------|--------------|--|--|--|--|--|
| Wavelength range:                       |  | 700 – 900 nm  |                |              |              |  |  |  |  |  |
| Pulse-length range @ 800 nm:            | ~10 - ~100 fs  | ~20 – ~200 fs | ~50 – ~500 fs  | ~0.3 – ~2 ps | ~0.5 – ~5 ps |  |  |  |  |  |
| Pulse-length range @ 1050 nm:           | ~8 – ~80 fs  | ~15 – ~80 fs  | ~30 – ~100 fs  | ~0.1 - ~1 ps | na           |  |  |  |  |  |
| Temporal resolution @ 800 nm:           | 3.7 fs   | 12 fs         | 17 fs          | 50 fs        | 90 fs        |  |  |  |  |  |
| Temporal resolution @1050 nm:           | 2 fs   | 9 fs          | 13 fs          | 41 fs        | na           |  |  |  |  |  |
| Delay increment <sup>1</sup> :          | 0.95 fs/pixel  | 0.85 fs/pixel | 1.145 fs/pixel | 11.5fs/pixel | 11.5fs/pixel |  |  |  |  |  |
| Temporal range <sup>3</sup> :           | 336 fs   | 480 fs        | 1.9 ps         | 19 ps        | 19 ps        |  |  |  |  |  |
| Spectral resolution @ 800 nm:           | 5 nm   | 4 nm          | 2 nm           | 0.23 nm      | 0.05 nm      |  |  |  |  |  |
| Spectral resolution @1050 nm:           | 6.5 nm   | 15 nm         | 7 nm           | 0.8 nm       | na           |  |  |  |  |  |
| Spectral range @ 800 nm <sup>3</sup> :  | 300 nm   | 160 nm        | 50 nm          | 8 nm         | 10 nm        |  |  |  |  |  |
| Spectral range @ 1050 nm <sup>3</sup> : | 400 nm   | 400 nm        | 125 nm         | 20 nm        | na           |  |  |  |  |  |
| Pulse complexity:                       | Time-bandwidth product < ~10   |               |                |              |              |  |  |  |  |  |
| Intensity accuracy:                     | 2%   |               |                |              |              |  |  |  |  |  |
| Phase accuracy:                         | 0.01 rad (intensity-weighted phase error)  |               |                |              |              |  |  |  |  |  |
| Single-shot possible?                   | Call us. <sup>2</sup> Yes; both free-running mode & triggered single-shot are now stan |               |                |              |              |  |  |  |  |  |
| Sensitivity (single-shot):              | Call us. <sup>2</sup> 1 µJ   |               |                |              |              |  |  |  |  |  |
| Sensitivity (at 10 <sup>3</sup> pps):   | 500µW(500nJ)   |               |                |              |              |  |  |  |  |  |
| Sensitivity (at 10 <sup>8</sup> pps):   | 50 mW (500 pJ)   |               |                |              |              |  |  |  |  |  |
| Spatial profile accuracy:               | <  | s)            |                |              |              |  |  |  |  |  |
| Spatial chirp accuracy (dx/dλ):         | 1 µm/nm  |               |                |              |              |  |  |  |  |  |
| Pulse-front tilt accuracy (dt/dx):      | 0.05 fs/mm   |               |                |              |              |  |  |  |  |  |
| Required input polarization:            | Any (just rotate GRENOUILLE!)  |               |                |              |              |  |  |  |  |  |
| Required input-beam diameter:           | 2 – 4 mm (collimated)  |               |                |              |              |  |  |  |  |  |
| Input-beam lateral-displacement         | >1 mm  |               |                |              |              |  |  |  |  |  |
| tolerance:                              | 21000  |               |                |              |              |  |  |  |  |  |
| Number of alignment knobs:              | : Zero   |               |                |              |              |  |  |  |  |  |
| Time to set up:                         | ~ 10 minutes   |               |                |              |              |  |  |  |  |  |
| Dimensions (L x W x H)                  | 33 cm x 7.5  | 33 cm x 7.5   | 33 cm x 4.5    | 45 cm x 7.5  | 61 cm x 7.5  |  |  |  |  |  |
| w/camera:                               | cm x 16.5 cm   | cm x 16.5 cm  | cm × 11.5 cm   | cm x 16.5 cm | cm x 16.5 cm |  |  |  |  |  |
| Weight:                                 | 3 kg   | 3 kg          | 1.2 kg         | 3 kg         | 6 kg         |  |  |  |  |  |

1. At full camera resolution.

2. The Model 8-9 can be modified to allow single-shot measurement, but at a reduction in sensitivity.

3. Temporal and spectral "ranges" are the full-scale ranges, not the pulse FWHM (which is typically a factor of 2 to 3 smaller).



### Comparison with LOLA UNIVERSITET (long several ps bunches)





- Simultaneous (almost, 30 min) measurement of bunch profile with transversely deflecting cavity LOLA (blue) and ORS (black).
- Initially the time calibration of • LOLA was off by 20 %, now fixed.
- OD2 Neutral density filter before • the Basler camera to prevent saturation
- smoothing and sqrt(ORS)
- Very good agreement of the recorded bunch length

**Optical Replica** 



# Undulator period

- Parameters
- Laser at 1130 nm
- Resonant between 110 and 160 MeV
- If period too short, filed is very low and hardly any wiggeling
- If too large, the field gets too large



 7.4 cm was chosen as a decent



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## FEMLAB 2D simulation

 Field pattern and field on axis, here choose B<sub>j</sub>=1T



 Gap between 30 and 50 mm suffices



### Field vs gap



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- Maximum gap to minimize effect on beam?
  - $B \sim B_{nax} exp(-gap/period)$

#### V. Ziemann: Optical Replica amd Laser Heater



#### Parameter list

| Energy    |        | 110    | 120    | 130    | 140    | 150    | 160    |
|-----------|--------|--------|--------|--------|--------|--------|--------|
| B0        | Т      | 0.1102 | 0.1497 | 0.1832 | 0.2136 | 0.2420 | 0.2691 |
| К         |        | 0.7615 | 1.0346 | 1.2662 | 1.4762 | 1.6725 | 1.8597 |
| A         | micron | 42     | 52     | 59     | 63     | 67     | 70     |
| gap(est.) | mm     | 51.0   | 45.0   | 39.5   | 36.5   | 33.7   | 30.9   |
|           |        |        |        |        |        |        |        |



# Synchronization



- Delay stages on laser table (Level 5)
  - crude: ~ns scale, mm-screw
  - delicate: ~ps scale, µm-screw
  - can we also delay the UV photons in case 'we' are too slow?
  - implications for photon routing in tunnel
- Lens to collimate photon beam
- Pulse stretcher to lengthen photon pulse
  simplify the longitudinal overlap



# Laser Vacuum System

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- Enter vacuum system on the table in laser room (window)
- Need only moderate vacuum to avoid
  - Convection, Schlieren effect
- Roughing pumps would suffice
  - easier, 'gadgets' need not be UHV compatible
- But ion pumps are preferred because they have no moving parts and avoid vibrations
- No baking foreseen
- Ion pums have an expected lifetime of minutes in rough vacuum
- Can we mechanically decouple the pumps from the mirror holders?
- Resonance frequency of long pipe? 110615 Desy V. Ziemann: Laser Heater Design Review



# Vacuum, 10L pump every 10 m

VAKTRAK: Laser Heater Beamline, r=3cm, 10 L pump/10m

P/Q(START) = 0.1287E-05/ 0.000 , P/Q(END) = 0.1287E-05/-0.2033E-19

AVERAGE P/Q = 0.1150E-05/ 0.1926E-19



• Assume outgassing 14e-10 torr l/s/cm<sup>2</sup> (Stainless steel after 10 h pumping)

- R. Elsey, Outgassing II, Vacuum 25, 347, 1975 V. Ziemann: Laser Heater Design Review

• Moderate pumping every 10m OK for 10<sup>-6</sup> torr



# Vacuum 10 L pump every 20 m

30

40



20

Z [M] • Enough for 3 10<sup>-6</sup> torr average pressure

10

• Looks like 10L pumps are ok

0



## Mirror Holders

- Must be stable (jitter and drift)
  - solidly bolted to the wall without extended support structure
- Mechanically decouple from long vacuum pipe
  - long bellow on either side
- Pointing capability to direct laser to next mirror
  - piezo- or stepper-motor driven mirror mounts
- Need capability to determine whether the laser hits the mirror
  - pin diode array with BPW34F probably works



## **BPW34F** sensitivity

**Relative Spectral Sensitivity** 

